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Substitute for form 1449/PTO

Sheet 2

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Complete if Known			
Application Number	10/678,438		
Filing Date	3 October 2003		
First Named Inventor	Vladimir V. MAKAROV		
Art Unit			
Examiner Name		_	
Attorney Docket Number	65 0305		

			U. S. PATEN	DOCUMENTS	
Examiner Initials*	Cite No. ¹	Document Number Number-Kind Code ^{2 (# known)}	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		^{US-} 6,031,299	02-29-2000	Keckley et al.	
		^{US-} 6.057.223	05-02-2000	Lanford et al.	
•		US- 6,140,655	10-31-2000	Russell et al.	
		^{US-} 6,322,672	11-27-2001	Shuman et al.	
		^{US-} 2002/0094694	07-18-2002	Russell et al.	
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages	Π
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Substitute for form 1449/PTO

Sheet 1

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Complete if Known			
Application Number	10/678,438		
Filing Date	3 October 2003		
First Named Inventor	Vladimir V. MAKAROV		
Art Unit			
Examiner Name			
Attorney Docket Number	65 0395		

	U. S. PATENT DOCUMENTS				
Examiner Initials*	Cite No.1	Document Number Number-Kind Code ^{2 (# known)}	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevan Figures Appear
	1	US- 5,840,630	11-24-1998	Cecere et al.	, , , , , , , , , , , , , , , , , , ,
	 				
	-	US- 6,514,866 B2	02-04-2003	Russell et al.	
		US- 2003/0060048 A1	03-27-2003	Russell et al.	
		^{US-} 2003/0038113 A1	02-27-2003	Makarov et al.	
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		^{US-} 6,509,276 B2	01-21-2003	Scott	
		^{US-} 5,798,529	08-25-1998	Wagner	
		US- 5,958,799	09-28-1999	Russell et al.	
		^{US-} 2001/0053605 A1	12-20-2001	Phaneuf et al.	
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		^{US-} 5,959,358	09-28-1999	Lanford et al.	

Examiner Cite Initials* No.1	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages		
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)	MM-DD-YYYY		Or Relevant Figures Appear	Т
		JP2295117	12-06-1990	NTT /		✓
		JP4173988	11-02-1990	Nissin Electric /		V
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Complete if Known Substitute for form 1449/PTO **Application Number** 10/678,438 INFORMATION DISCLOSURE Filing Date 3 October 2003 STATEMENT BY APPLICANT **First Named Inventor** Vladimir V. MAKAROV Art Unit (Use as many sheets as necessary) **Examiner Name** Attorney Docket Number Sheet 13 65.0395

Examiner	Cite	NON PATENT LITERATURE DOCUMENTS Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of	
Initials*	No.1	the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		S. Herschbein et al., The Challenges of FIB Chip Repair & Debug Assistance in the 0.25 um Copper Interconnect Millenium, Proceedings from 24th International Symposium for Testing and Failure Analysis, 15-19 November 1998, Dallas, Texas, pp.127-130	
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		V. Makarov et al., Dry Etching Considerations for Copper Metallizations, Proceedings of the 4th AVS International Conference on Microelectronics and Interfaces, March 3-6, 2003 Santa Clara, California, USA, pp 198-200	
		H. Bender et al., Focused Ion Beam Analysis of Organic Low-k Dielectrics, Proceedings from the 26th International Symposium for Testing and Failure Analysis, 12-16 November 2000, Bellevue, Washington, USA, pp. 397-405	
		T. Stark et al., H20 enhanced focused ion beam micromachining, J. Vac. Sci. Technol. B 13(6), Nov/Dec 1995, pp. 2656-2569	
		P. Ho et al., Overview on Low Dielectric Constant Materials for IC Applications, in Low Dielectric Constant Materials for IC Applications, Ed. by P. Ho et al., Springer-Verlag, Berlin, Heidelberg 2003, Chapter I, pp. 1-21	
		J. Gonzalez et al., Chemically enhanced focused ion beam micromachining of copper, J. Vac. Sci. Technol. B 19(6), Nov/Dec 2001, pp. 2539-2542	

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	1	NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		J. Gonzalez et al, Improvements in Focused Ion Beam Micro-machining of Interconnect Materials, J. Vac. Sci. Technol. B20(6), Nov/Dec 2002, pp. 2700-2704	
		L. Harriott, Digital scan model for focused ion beam induced gas etching, J. Vac. Sci. Technol. B 11(6), Nov/Dec 1993, pp. 2012-2015	
		R. Lee et al., Low Resisitivity FIB Depositions Within High Aspect Ratio Holes, Proceedings of the 22nd International Symposium for Testing and Failure Analysis, 8-22 November 1996, Los Angeles, California, pp. 85-88	
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		K. Edinger, Gas assisted etching of copper with focused ion beams, J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999, pp. 3058-3062	
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		IDS P3X brochure, Schlumberger, printed 10/99, two pages	
		Y. Igarashi et al., Dry Etching Technique for Subquarter-Micron Copper Interconnects, J. Electronchem. Soc., Vol. 142, No. 3, March 1995, pp. L36-L37	
		S. Pauthner, Device modification and gass assisted etching on Cu-samples, 3rd European FIB Users Group Meeting (EFUG99) Abstracts 4 October 1999 (1 paragraph abstract of 8-page document)	
		2-Nitroethanol Material Safety Data Sheet, Aldrich Chemical Co., Inc., valid 02/2003-04/2003, (four pages)	

Examiner	Date
Signature	Considered

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Complete if Known

Application Number 10/678,438

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

First Named Inventor Vladimir V. MAKAROV

Art Unit

Examiner Name

(Use as many sheets as necessary)

Sheet 5 of 5 Attorney Docket Number 65.0395

	T =	NON PATENT LITERATURE DOCUMENTS	
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		N. Goldblatt et al., Unique and Practical IC Timing Analysis Tool Utilizing Intrinsic Photon Emission, Microelectronics Reliability Conference, 2001, 41(9-10): 1507-1512	_
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		T. Lundquist et al., Ultra-Thinning of C4 Integrated Circuits for Backside Analysis during First Silicon Debug, Microelectronics Reliability Conference, 2001, 41(9-10): 1545-1549	
		T. Lundquist et al., Characterize Gate-Level Transistor Performance with PICA, Seminconductor International, 2001, 4 pages	
<u></u>		C. Musil et al., Focused Ion Beam Microsurgery for Electronics, IEEE Electron Device Letters, 1986, EDL-7(5):285-287	

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